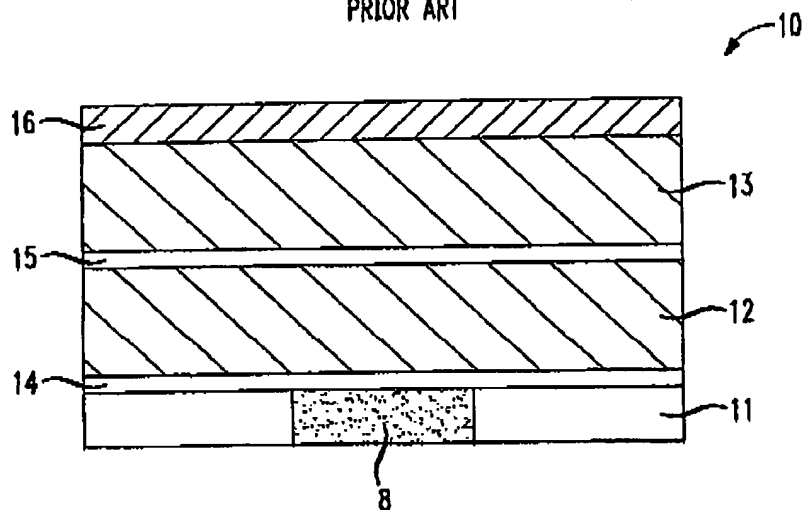


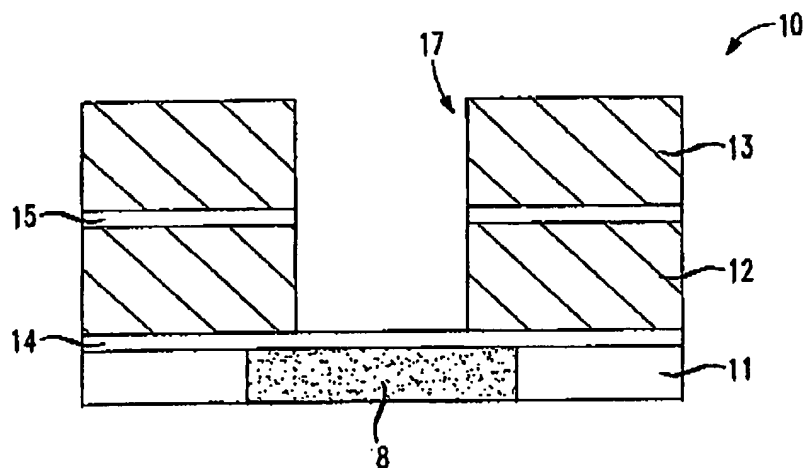
HUANG 5-8-5-2-2-25-3  
A Mask Layer and Interconnect Structure for Dual Damascene Fabrication of a Semiconductor Device  
Robert L. Wolter (407-926-7700)  
Serial #10/026,257

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**FIG. 1**  
PRIOR ART



**FIG. 2**  
PRIOR ART



HUANG J-S-J-Z-Z-Z-J  
 A Mask Layer and Interconnect Structure for Dual Damascene Fabrication of a Semiconductor Device  
 Robert L. Walter (407-926-7700)  
 Serial #10/026,257

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FIG. 27

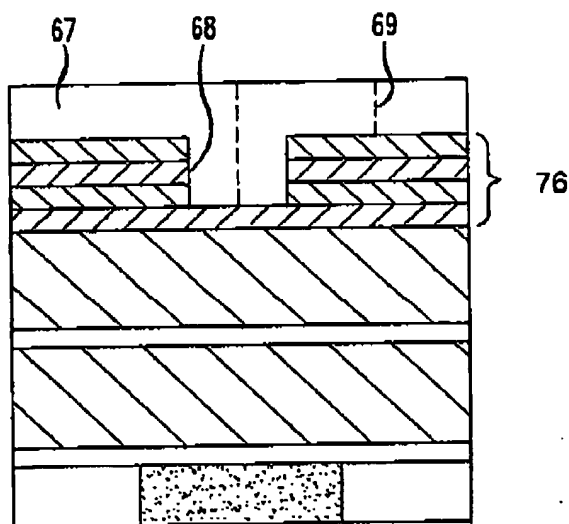
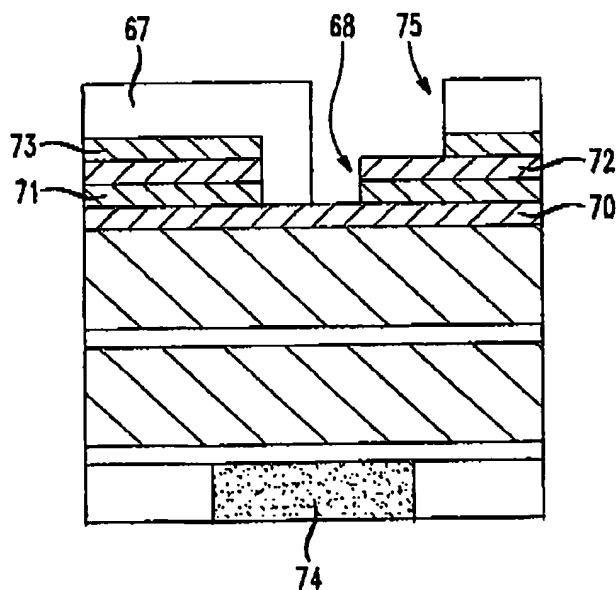


FIG. 28



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